

Listing of Claims:

1-35. (Cancelled).

36. (Original) A nanostructure comprising:

(a) a substrate having a surface;

(b) a patterned imaging layer of self-assembled monolayer on the surface of the substrate having a pattern therein of separated regions with a spacing of the regions of 100 nm or less;

(c) a block copolymer layer on the imaging layer, the block copolymer layer having separated regions of one component of the copolymer that coincide with the separated regions on the imaging layer.

37. (Original) The microstructure of Claim 36 wherein the thickness of the copolymer layer is 100 nm or less.

38. (Original) The microstructure of Claim 36 wherein the substrate is formed of single crystal silicon.

39. (Original) The microstructure of Claim 36 wherein the imaging layer is an alkylsiloxane self-assembled monolayer.

40. (Original) The microstructure of Claim 36 wherein the imaging layer is an octadecyltrichlorosilane self-assembled monolayer.

41. (Original) The microstructure of Claim 36 wherein the copolymer layer is a copolymer of polystyrene and poly(methyl methacrylate).